

Ultrawide Bandgap Semiconductors: Influence of Material Properties on Power Device Performance

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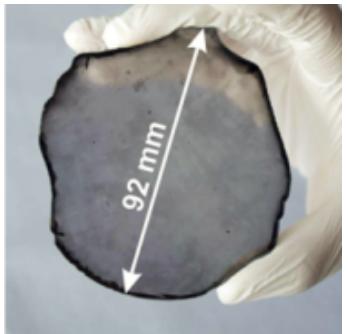
Stanford: Srabanti Chowdhury

August 24, 2022

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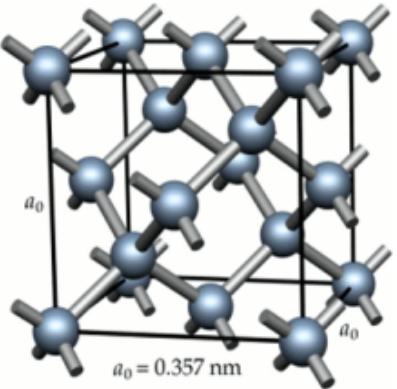


ULTRA Semiconductors



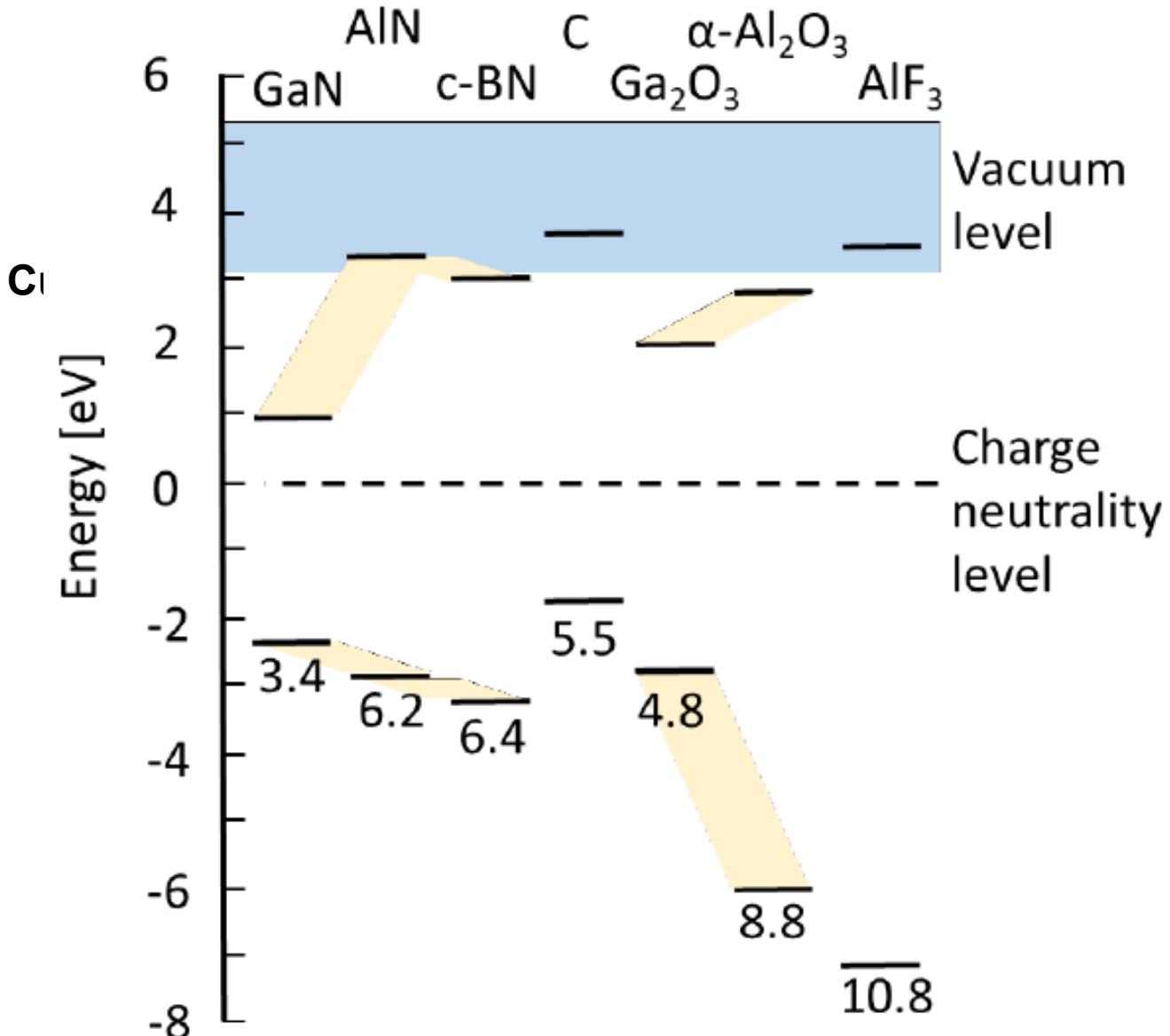
Augsburg Univ.

Diamond Cubic



- $E_g = 5.5$ eV
- sp^3 bonded carbon
- C – 6e
- Diamond Cubic

$a = 3.57 \text{ \AA}$



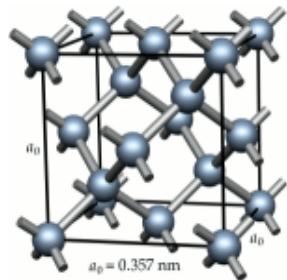
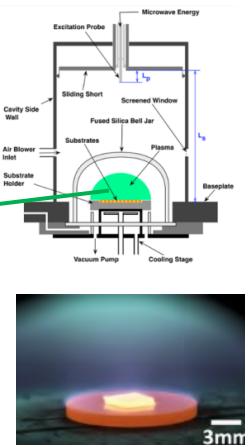
exaTech

G. L. Doll, J. A. Sell, C. A. Taylor II, and R. Clarke, Phys. Rev. B, **43**, 6816 (1991).

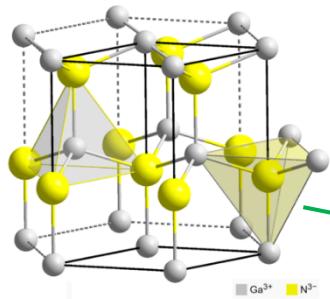




MPCVD

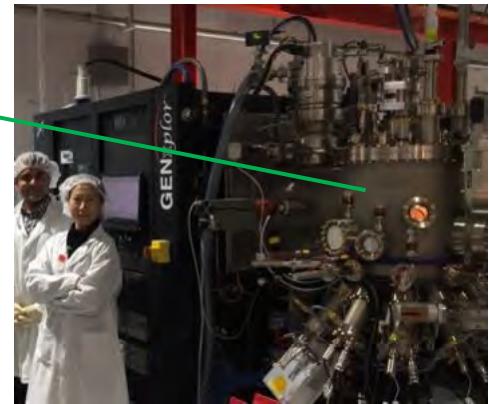


Diamond

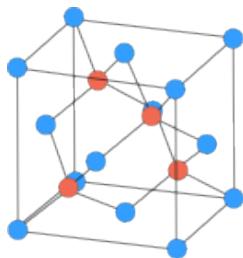
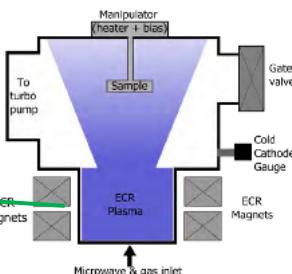


AlN and $(\text{B}_x\text{Al}_{1-x}\text{N})$

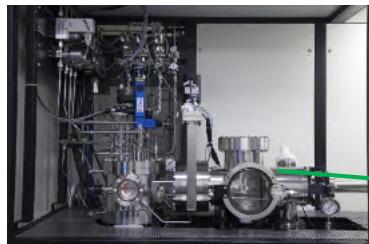
MBE



ECR-MPCVD



c-BN



AlGaN

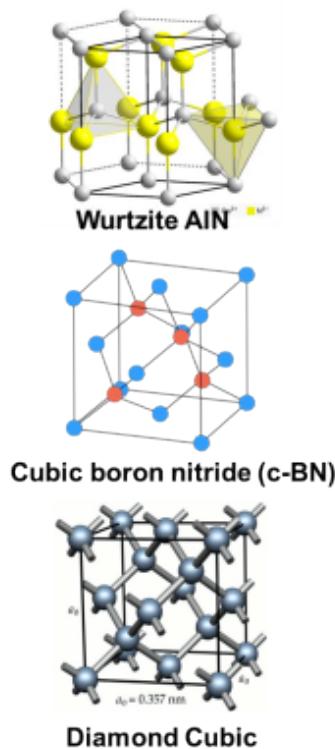


MOCVD

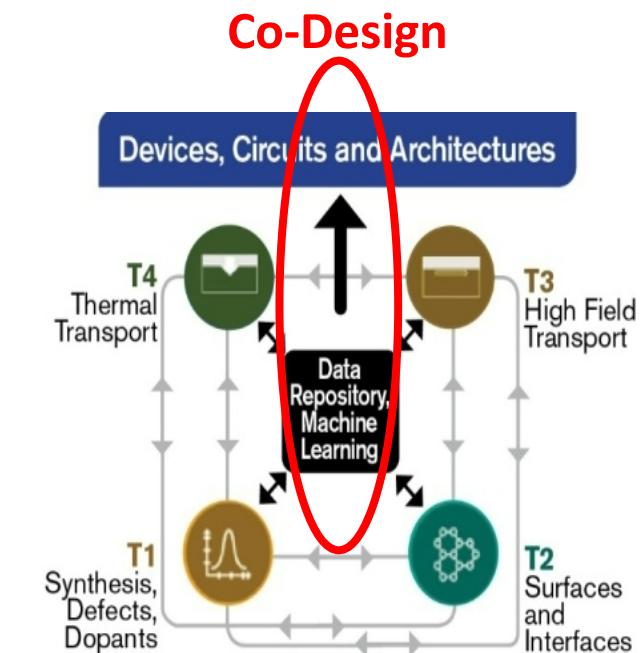
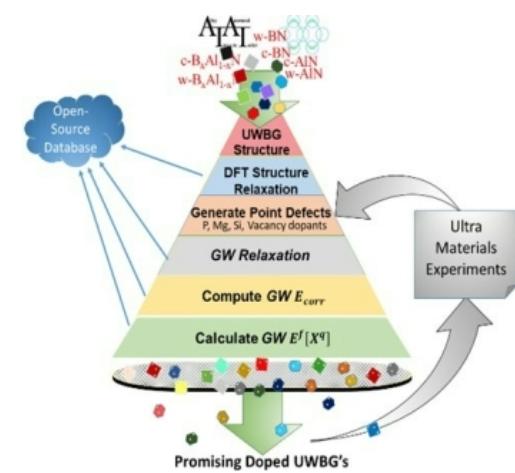


ULTRA EFRC

Mission: To achieve extreme electrical properties and phenomena through fundamental understanding of ultra wide bandgap materials, which will enable a resilient, smart electricity grid.

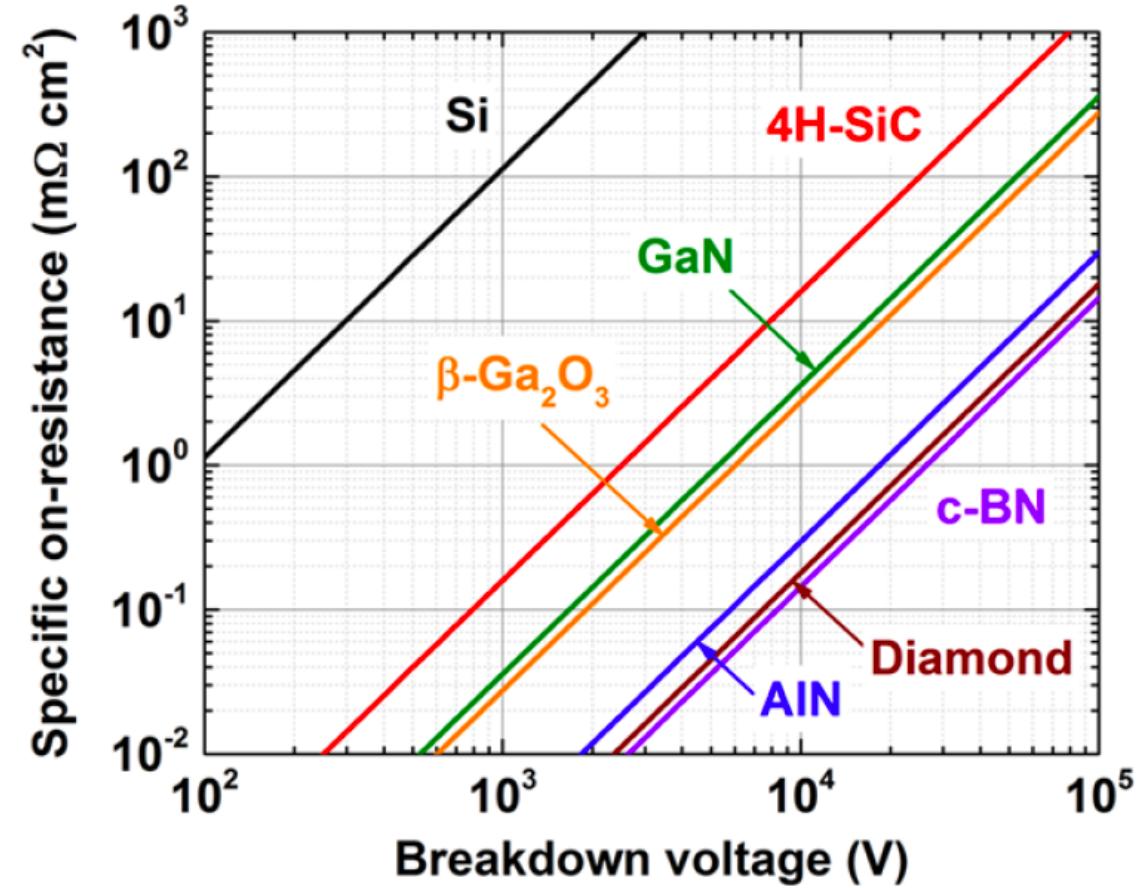
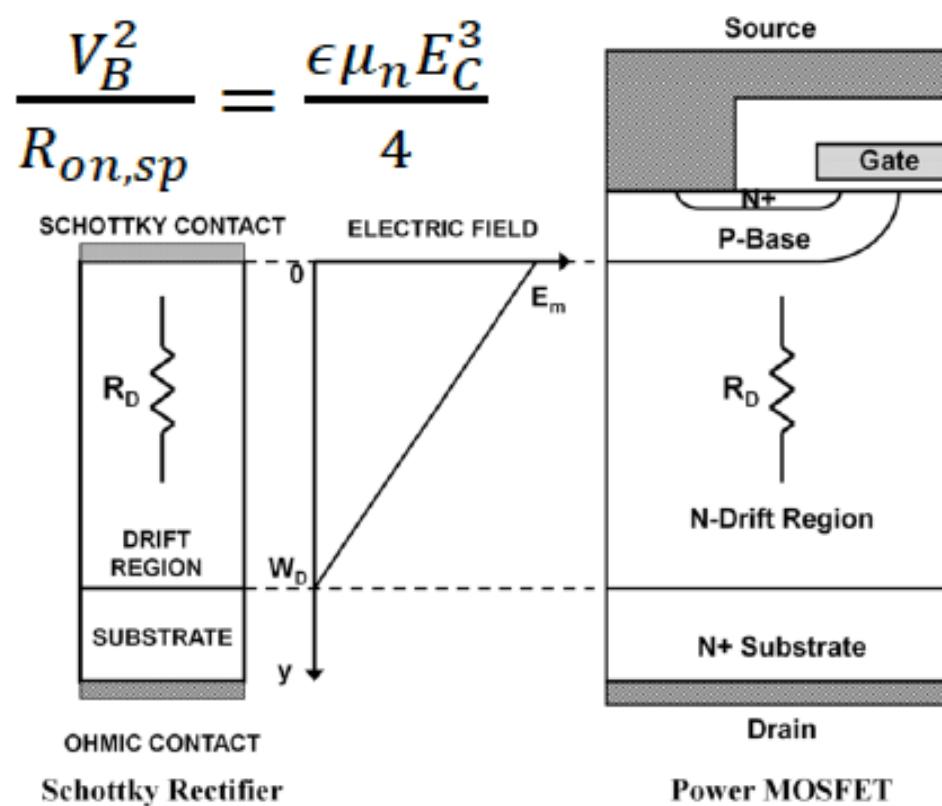


- **Methodology**
 - Close integration of theory and computational methods throughout
 - Materials synthesis, defect and impurity physics
 - Interfaces, atomic scale and electronic states characterization
 - High field electronic transport and breakdown characterization
 - Thermal transport theory and measurement
- **Future Grid Co-Design Ecosystem**
 - Provides a knowledge base enabling communication across all levels of the technology



Impact on Power Electronics: Baliga* Figure of Merit

There are two main parameters of importance for power electronics, the breakdown voltage (related to the critical field, E_C for impact ionization), and the specific on-resistance



*Baliga B J 1982 Semiconductors for high voltage vertical channel field effect transistors J. Appl. Phys. 53 1759–64



Impact on Power Electronics: Baliga* Figure of Merit

The *unipolar* FOM is widely used to compare materials of power electronic applications, based on two important quantities: the reverse breakdown voltage, V_B , and the forward specific on-resistance, $R_{on,sp}$:

$$FOM = \frac{V_B^2}{R_{on,sp}}$$

For Ohmic conduction, $R_{on,sp}$ is connected to the semiconductor material through the electron (hole) density, $n(p)$, the carrier mobility, $\mu_{n,p}$, and the drift region width, W_d :

$$R_{on,sp} = \frac{W_d}{q\mu_{n,p}(n, p)}$$

The breakdown voltage depends on the breakdown (critical) field, $V_B = \eta \mathcal{E}_{cr} W_d$, which varies as the square of the bandgap

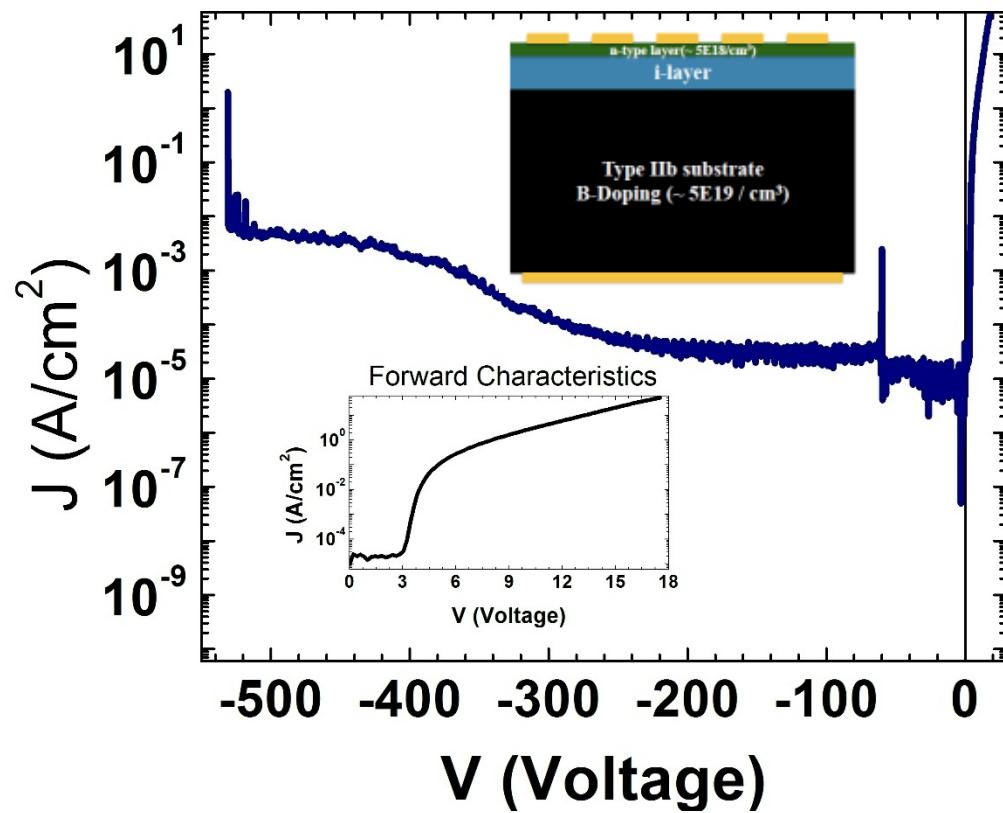
	Narrow	Wide	ULTRAs – New class of materials				
	Si	4H-SiC	GaN	$\beta\text{-Ga}_2\text{O}_3$	Diamond	h-AlN	h-BN
Bandgap (eV)	1.12	3.26	3.4	4.9	5.5	6.2	6.4
Breakdown Field (MV/cm)	0.3	2.5	3.8	8	10	16	12
Baliga's figure of merit (FOM)	1	183	535	3444	9000	9797	1678

Traditional New Emerging Technology

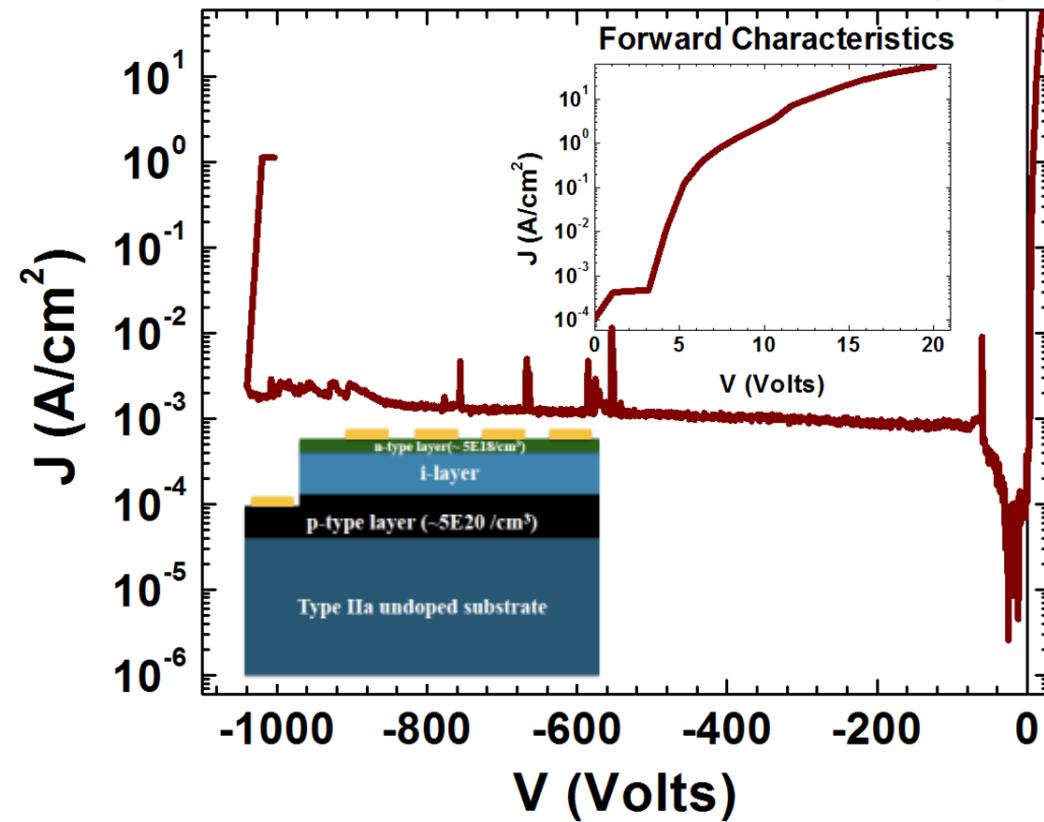
From M. Kuball, EFRC highlight 2020



Breakdown in Diamond SPIN Diodes



- Type IIb substrate with ~ 3.5 micron i-layer
- Forward Current Density $\sim 50 \text{ A}/\text{cm}^2$ at 17 V
- Breakdown voltage $\sim 530 \text{ V}$ at $1\text{E}-2 \text{ A}/\text{cm}^2$

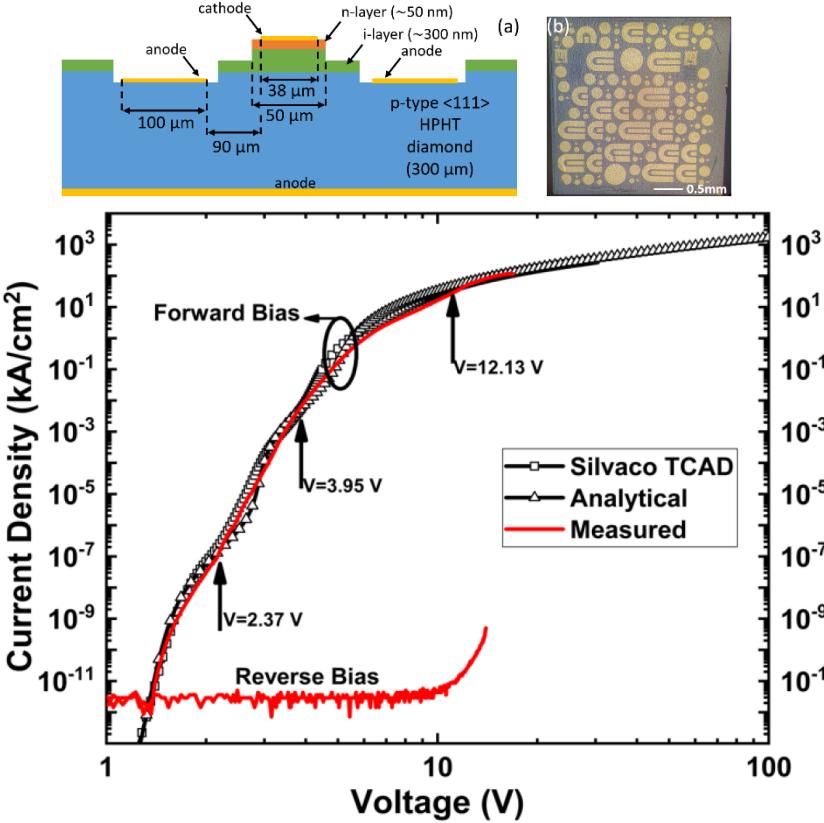


- Type IIa substrate with ~ 8.5 micron i-layer
- Forward Current Density $\sim 55 \text{ A}/\text{cm}^2$ at 20 V
- Breakdown voltage $\sim 1040 \text{ V}$ at $1\text{E}-3 \text{ A}/\text{cm}^2$

\square < 10 \square / \square

Forward Characteristics of Diamond SPIN Diodes

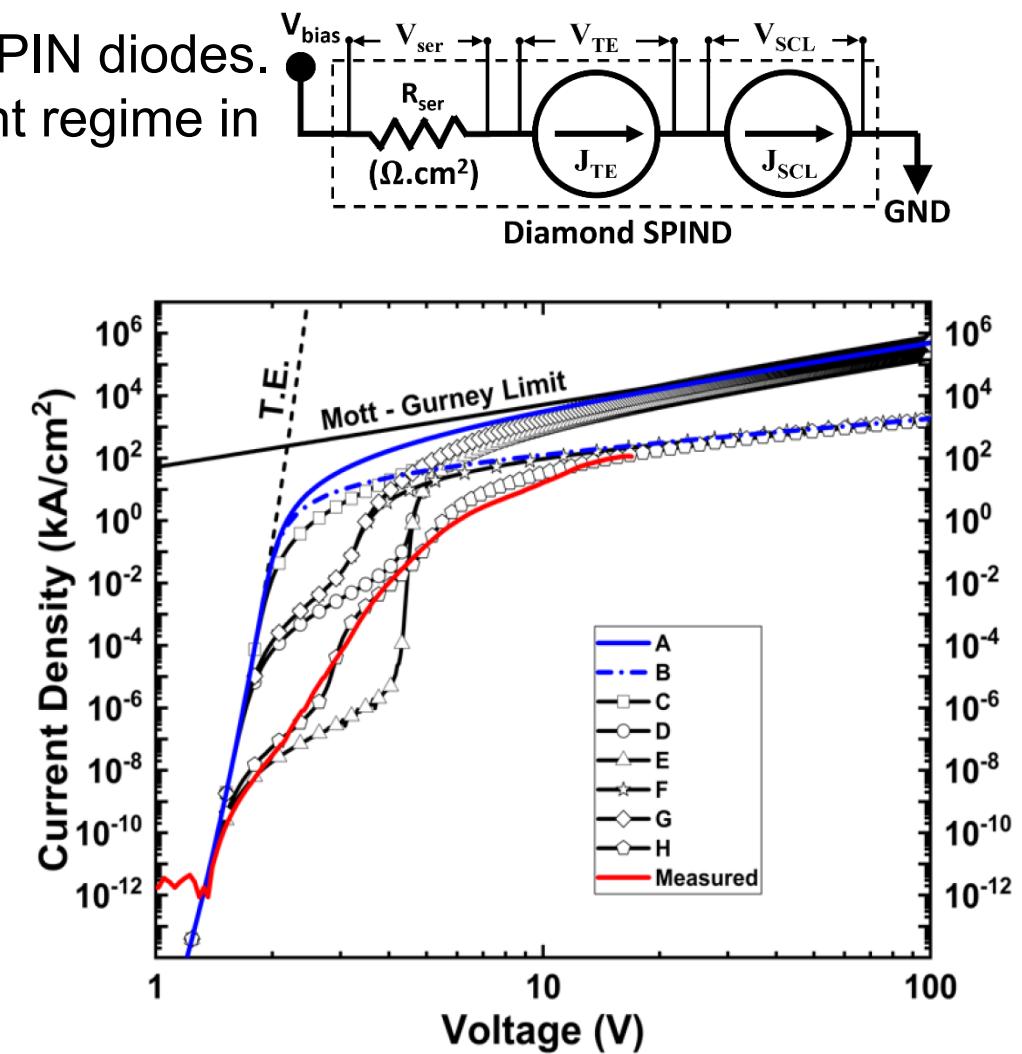
Record forward current (116 kA/cm^2) measured in Schottky PIN diodes. Strong evidence of Mott-Gurney space charge limited current regime in forward bias including trap effects.



$$J = \frac{9}{8} \epsilon \mu_p \frac{V^2}{d^3}$$

The schematic diagram shows the diamond SPIN diode structure with various bias voltages: V_{bias} , V_{ser} , V_{TE} , V_{SCL} , and GND . The current paths are labeled J_{TE} and J_{SCL} . A resistor R_{ser} is shown in series with the diode. The carrier density is given as $(\Omega \cdot \text{cm}^2)$.

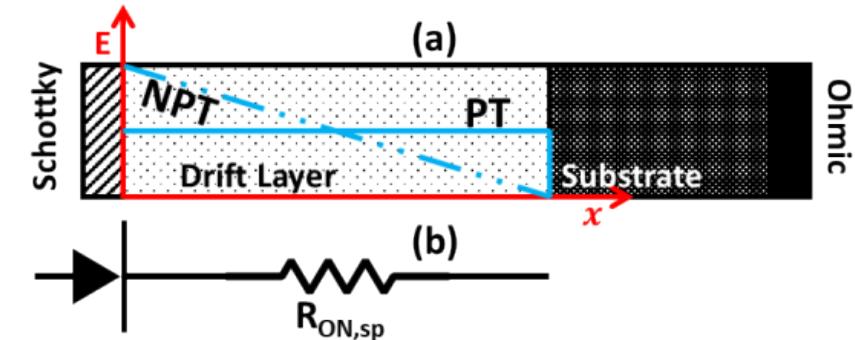
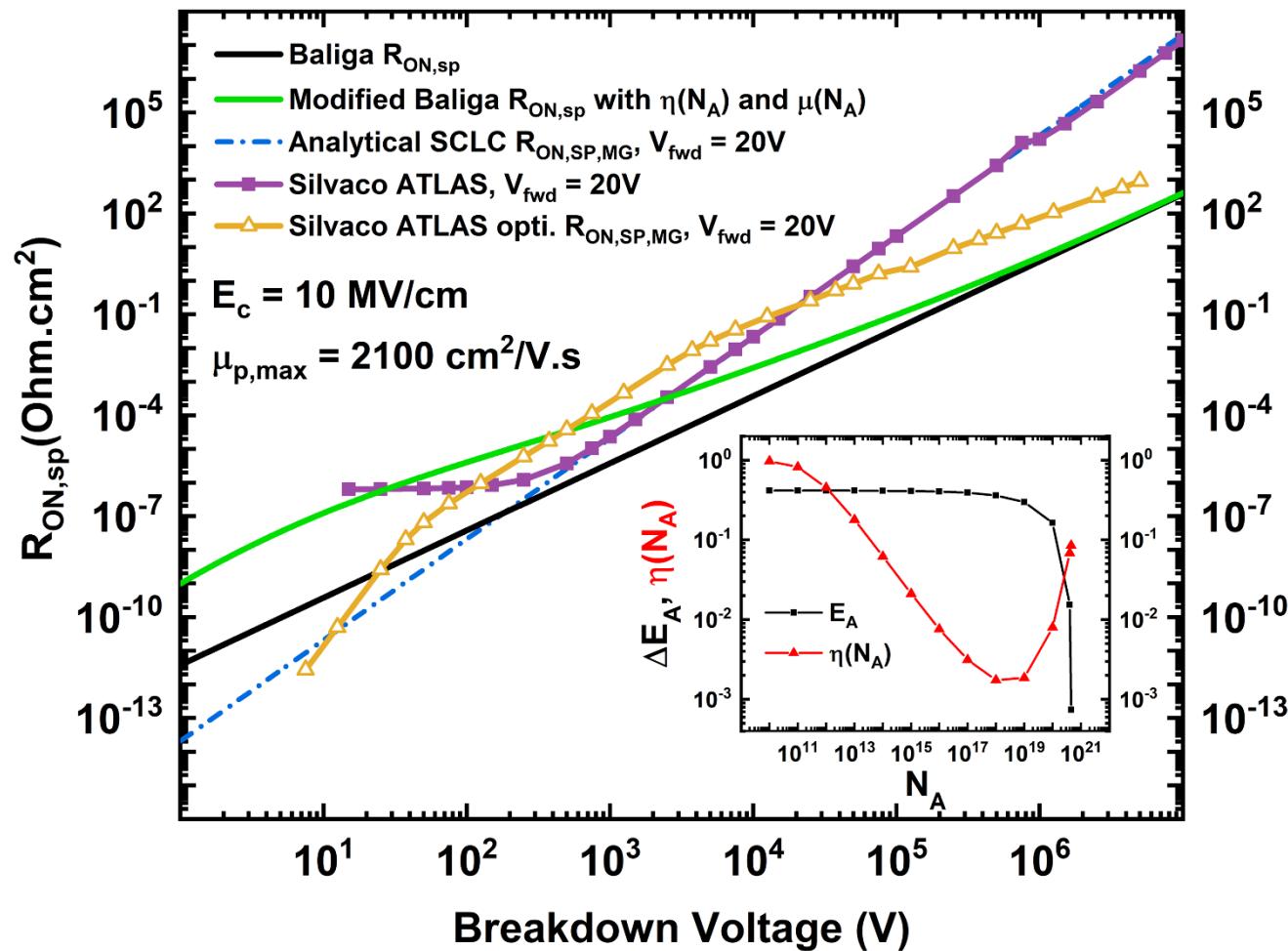
3 Trap model explains jumps in the J-V characteristics, and limitations compared to ideal behavior



H. Surdi, F. A. M. Koeck, M. F. Ahmad, T. J. Thornton, R. J. Nemanich, and S. M. Goodnick, *IEEE Trans. Elec. Dev.* 69(1), 254-261 (2022)



Power Electronic Figure of Merit (FOM) Revisited



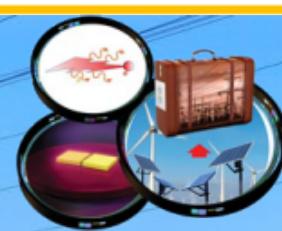
Incomplete Ionization

$$R_{ON,sp} = \frac{d}{q\mu(N_A^-)N_A^-}$$

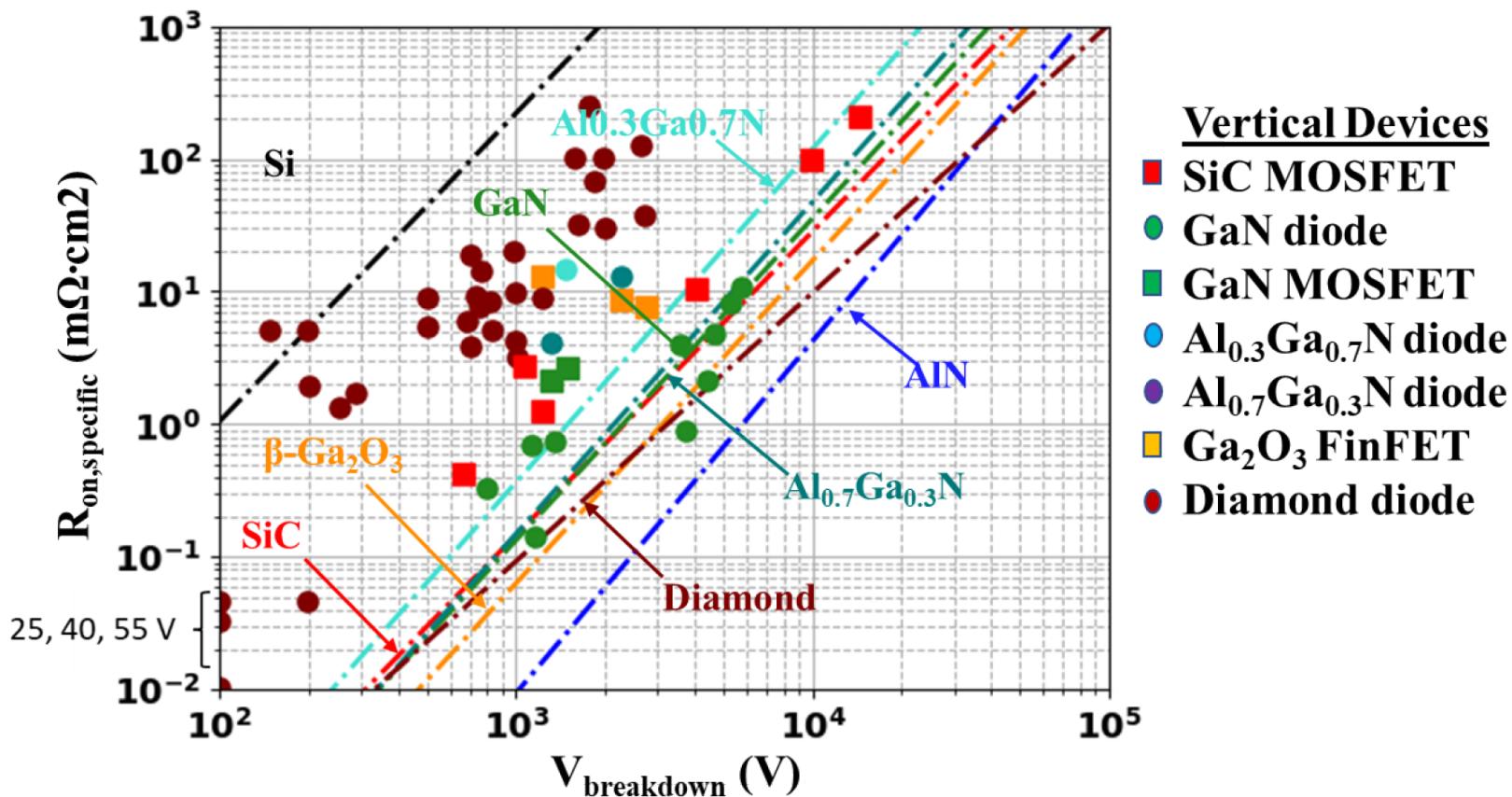
Mott-Gurney

$$R_{ON,sp,MG} = \frac{4}{9\epsilon_r\epsilon_0\mu} \frac{d^3}{V}$$

Note: FOM no longer given by $\frac{V_B^2}{R_{on,sp}}$ for non-Ohmic I-V



Comparison Between Materials and to Experimental



Data points taken from A. J. Green, J. Speck, G. Xing, et al., “ β -Gallium Oxide Power Electronics,” APL Mater. 10, 029201 (2022), and various other references



Other FOMs Under Investigation

$$P_{loss,min} = \frac{4I_{rms}(V_B V_D)^{3/4}}{E_C \sqrt{\mu}} \sqrt{\frac{kI_D f}{i_{g,av}}}$$

Huang Material Figure of Merit



Si-based converter

WBG-based converter

UWBG-based converter

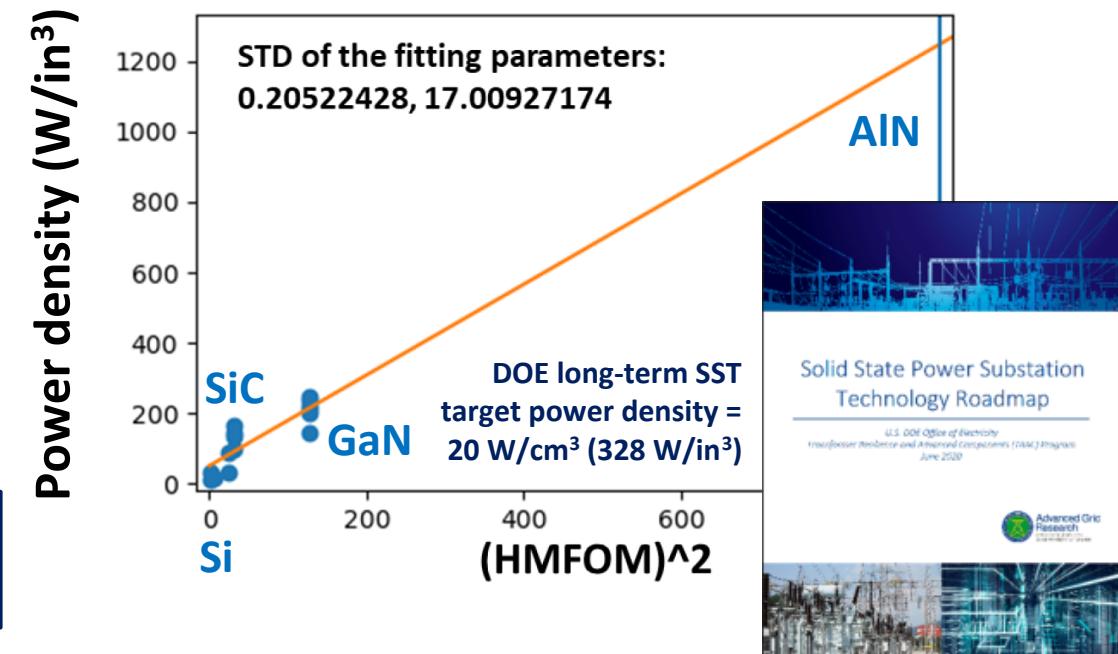
Need to also take into account thermal properties – other FOMs are applicable

$$\frac{f}{E_C^2 \mu} = \text{Constant}$$

Presently being evaluated!

Power Density $\sim f$
 $\sim E_C^2 \mu = \text{HMFOM}^2$

HMFOM² vs Power Density

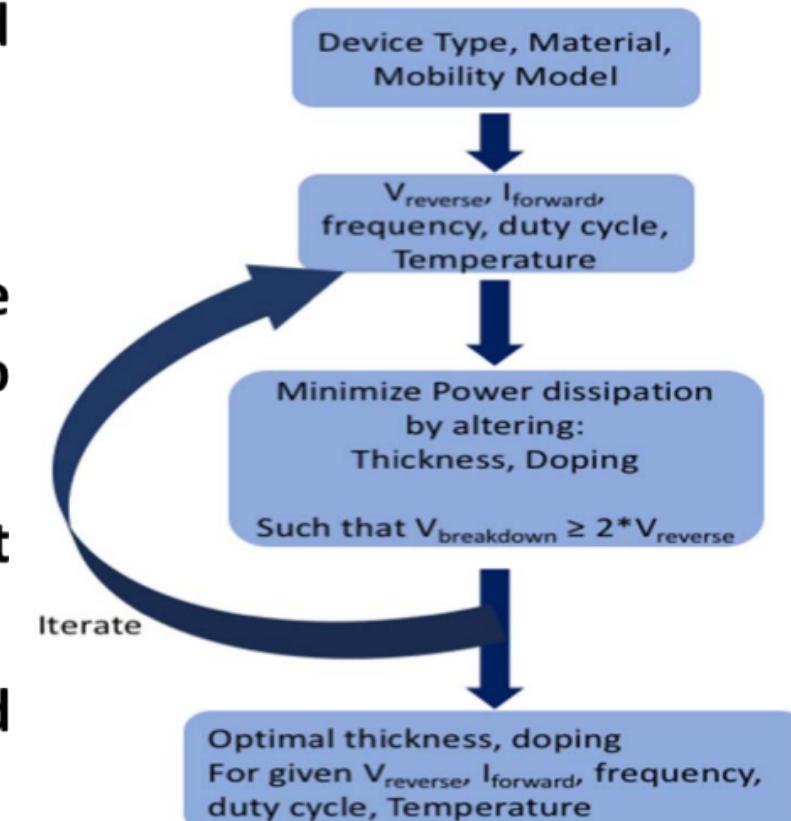


PIN and SBD Diode Power Loss Optimization

- For a given set of operating parameters, the doping level and drift thickness are optimized to minimize power loss:

$$P_{total} = P_{forward} + P_{reverse} + P_{dynamic} + P_{displacement}$$

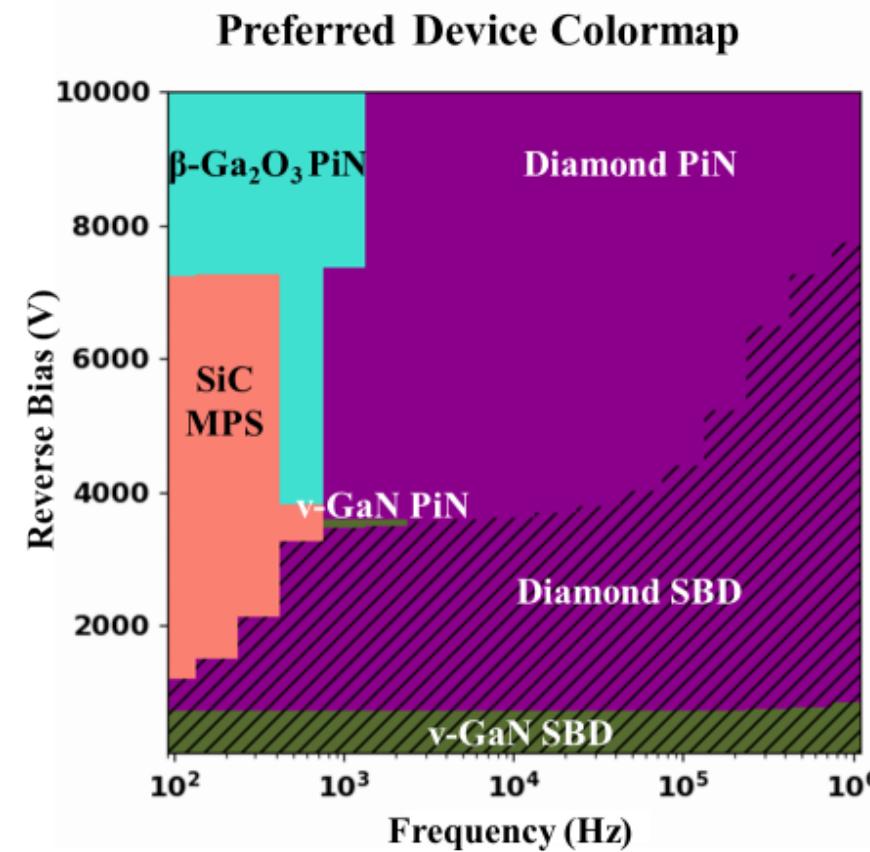
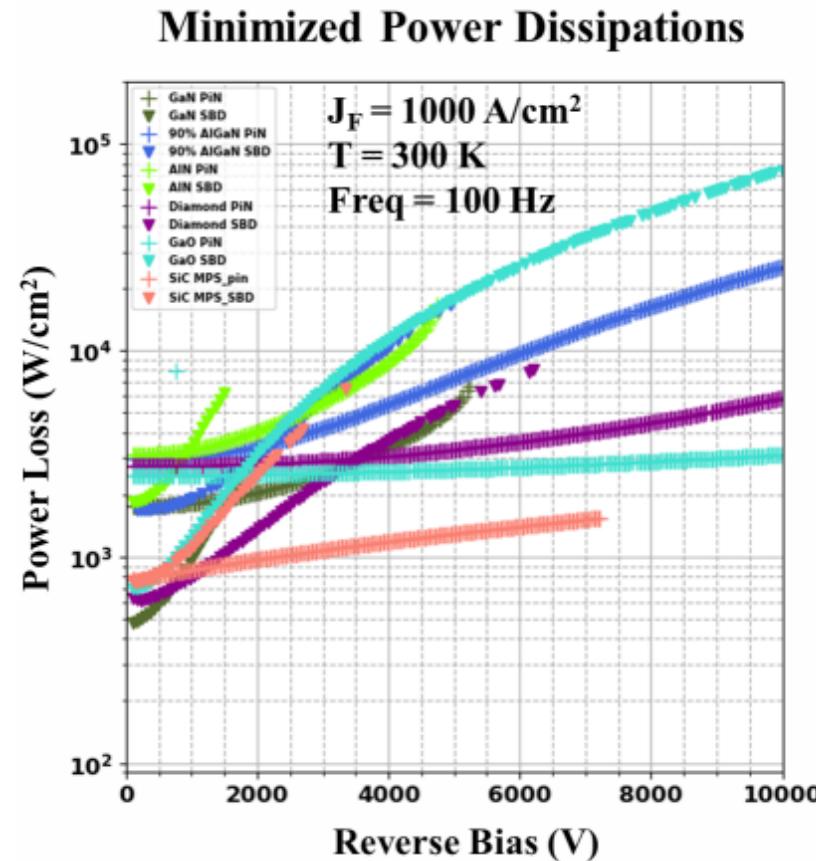
- The temperature- and doping-dependent mobilities are calculated theoretically or with empirical models fit to experiment
- The temperature-, doping-, and drift thickness-dependent critical fields are calculated from the ionization integral*
- UWBG-specific effects such as incomplete ionization and space-charge limited current are included



*J. Cooper et al., EDL 41(6) 892 (2020)

PIN and SBD Diode Power Loss Optimization

- The UWBG material and diode type (PIN or Schottky) that produces the lowest power loss for each reverse bias and frequency is plotted in a color-map



Summary

- Ultra-materials ($E_g > 5 \text{ eV}$) hold promise for achieving high Figure of Merit (FOM) for power electronics applications
- Current materials are still immature in terms of unwanted defects (premature breakdown, low mobility) and challenges in doping (incomplete ionization)
- Figure of Merit is one (incomplete) way to relate semiconductor material properties to device performance
 - Conventional approach to calculating FOM (e.g. Baliga FOM) has been oversimplified, and only address particular applications of power electronics
 - Current work through the co-design thrust of the ULTRA EFRC attempts to correct some of the shortcomings of particular importance for UWBGs
 - New performance metrics in terms of power dissipation in switching power converter applications are currently being developed



Thanks!



